

## **In the Claims**

This listing of claims will replace all prior versions, and listings, of claims in the application:

## **Listing of Claims**

1. (original) A method of creating an interface layer over the surface of a semiconductor device, comprising the steps of:

providing a semiconductor device, said semiconductor device having a first and a second surface with points of electrical contact to said semiconductor device having been provided in said second surface of said semiconductor device, said semiconductor device having been provided with a layer of passivation over said second surface of said semiconductor device, openings having been created through said layer of passivation exposing said points of electrical contact to said semiconductor device;

providing a semiconductor device mounting support having a first and a second surface, contact pads having been provided in said first or said second surface of said semiconductor device mounting support;

positioning said semiconductor device over the second surface of said semiconductor device mounting support, said first surface of said semiconductor device facing said second surface of said semiconductor device mounting support;

providing conductive interconnections between said points of electrical contact provided in said second surface of said semiconductor device and contact pads provided over the second surface of said semiconductor device mounting support;

providing an underfill for said semiconductor device;

depositing an interface layer over the surface of said layer of passivation; and  
patterning and etching said interface layer, creating at least one opening through said interface layer.

**2. (currently amended)** The method of claim 1, wherein said interface layer comprising ~~polysilicon~~ polyimide.

**3. (original)** The method of claim 1, further comprising depositing a layer of mold compound over the surface of said interface layer, filling said at least one opening created through said interface layer.

**4. (original)** A method of creating protective layers for the packaging of a semiconductor device, comprising the steps of:

providing a semiconductor device, said semiconductor device having a first and a second surface with points of electrical contact to said semiconductor device having been provided in said second surface of said semiconductor device, said

semiconductor device having been provided with a layer of passivation over said second surface of said semiconductor device, openings having been created through said layer of passivation exposing said points of electrical contact to said semiconductor device;

providing a semiconductor device mounting support having a first and a second surface, contact pads having been provided in said first or said second surface of said semiconductor device mounting support;

positioning said semiconductor device over the second surface of said semiconductor device mounting support, said first surface of said semiconductor device facing said second surface of said semiconductor device mounting support;

providing conductive interconnections between said points of electrical contact provided in said second surface of said semiconductor device and contact pads provided over the second surface of said semiconductor device mounting support;

providing an underfill for said semiconductor device;

depositing an interface layer over the surface of said

layer of passivation;

patterning and etching said interface layer, creating at least one opening through said interface layer; and

depositing a layer of mold compound over the surface of said interface layer, filling said at least one opening created through said interface layer.

**5. (currently amended)** The method of claim 4, wherein said interface layer comprising ~~polysilicon~~ polyimide.

**6-10. (cancelled)**

**11. (currently amended)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor surface, ~~said semiconductor surface comprising at least one completed semiconductor device, said at least one completed semiconductor device being densely packed and having a relatively large surface area;~~

depositing a stress relief interface layer over said semiconductor surface; and

creating at least one opening through said stress relief interface layer.

**12. (original)** The method of claim 11, said semiconductor surface being a surface of a semiconductor device.

**13. (original)** The method of claim 11, said stress relief interface layer relieving stress introduced by mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.

**14. (currently amended)** The method of claim 11, wherein said stress relief interface layer comprising ~~polysilicon~~ polyimide.

**15. (original)** The method of claim 11, further comprising depositing a layer of mold compound over the surface of said stress relief interface layer, filling said at least one opening created through said stress relief interface layer.

**16. (original)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor surface;

depositing a stress relief interface layer over said semiconductor surface;  
creating at least one opening through said stress relief interface layer; and  
depositing a layer of mold compound over the surface of said stress relief interface layer,  
filling said at least one opening created through said stress relief interface layer.

**17. (original)** The method of claim 16, said semiconductor surface being a surface of a semiconductor device.

**18. (original)** The method of claim 16, said stress relief interface layer relieving stress introduced by mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.

**19. (currently amended)** The method of claim 16, wherein said stress relief interface layer comprising ~~polysilicon~~ polyimide.

**20. (currently amended)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor surface, ~~said semiconductor surface comprising at least one completed semiconductor device, said at least one completed semiconductor device being densely packed and having a relatively large surface area;~~

depositing a layer of ~~polysilicon~~ polyimide over said semiconductor surface; and

creating at least one opening through the layer of ~~polysilicon~~ polyimide.

**21. (original)** The method of claim 20, said semiconductor surface being a surface of a semiconductor device.

**22. (currently amended)** The method of claim 20, wherein said layer of ~~polysilicon~~ polyimide relieving stress introduced by mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.

**23. (currently amended)** The method of claim 20, further comprising depositing a layer of mold compound over the surface of said layer of ~~polysilicon~~ polyimide, filling said at least one opening created through said layer of ~~polysilicon~~ polyimide.

**24. (currently amended)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor surface;

depositing a layer of ~~polysilicon~~ polyimide over the surface of said semiconductor surface;

creating at least one opening through said layer of ~~polysilicon~~ polyimide; and

depositing a layer of mold compound over the surface of said layer of ~~polysilicon~~ polyimide, filling said at least one opening created through said layer of ~~polysilicon~~ polyimide.

**25. (original)** The method of claim 24, said semiconductor surface being the surface of a semiconductor device.

**26. (currently amended)** The method of claim 24, wherein said layer of ~~polysilicon~~ polyimide relieving stress introduced mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.

**27. (currently amended)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor device;

depositing a layer of ~~polysilicon~~ polyimide over a surface of said semiconductor device;

and

creating at least one opening through the layer of ~~polysilicon~~ polyimide.

**28. (currently amended)** The method of claim 27, wherein said layer of ~~polysilicon~~ polyimide relieving stress introduced by mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.

**29. (currently amended)** The method of claim 27, further comprising depositing a layer of mold compound over the surface of said layer of ~~polysilicon~~ polyimide, filling said at least one opening created through layer of ~~polysilicon~~ polyimide.

**30. (currently amended)** A method for applying a stress relief interface layer over a semiconductor surface, comprising the steps of:

providing a semiconductor device;

depositing a layer of ~~polysilicon~~ polyimide over a surface of said

semiconductor device;

creating at least one opening through said layer of ~~polysilicon~~ polyimide; and

depositing a layer of said compound over the surface of said layer of ~~polysilicon~~ polyimide, filling said at least one opening created through said layer of ~~polysilicon~~ polyimide.

**31. (currently amended)** The method of claim 30, wherein said layer of ~~polysilicon~~ polyimide relieving stress introduced by mismatched Coefficients of Thermal Expansion (CTE) of thermally interacting layers.